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(71) Applicants (for all designated States except US): AUS-TRALIAN PHOTONICS PTY LTD [AU/AU]; 201 National Innovation Centre, Australian Technology Park, Eveliegh, New South Wales 1430 (AU). THE UNIVER-SITY OF SYDNEY [AU/AU]; Parramatta Road, Sydney, New South Wales 2006 (AU).

(72) Inventors; and

(75) Inventors/Applicants (for US only): SCEATS, Mark [AU/AU]; 102/38 Refinery Drive, Pyrmont, New South Wales 2006 (AU). STEPANOV, Dmitrii, Yu [RU/AU]; 7/126 Croydon Avenue, Croydon Park, New South Wales 2133 (AU).

(74) Agent: FREEHILLS CARTER SMITH BEADLE; Level 32, MLC Centre, 19-29 Martin Place, Sydney, New South Wales 2000 (AU).

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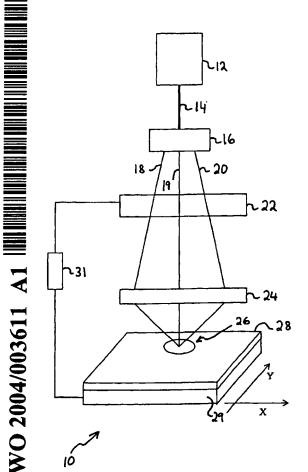
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(54) Title: WRITING OF PHOTO-INDUCED STRUCTURES



(57) Abstract: A method of writing a photo-induced structure into a photosensitive material substrate, the method comprising the steps of creating an interference pattern utilising at least two light beams, exposing the substrate to the interference pattern for photo-inducing material changes in the substrate, and creating an irregularity in the interference pattern by controlling a wavefront of at least one of the beams, for creating a functional defect in the photo-induced structure.